Atty Docket No. MLSE 1060-1

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/Brianna Dahlberg/ Brianna Dahlberg

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Torbjörn Sandström

Application No. 10/579,511

Confirmation No. 6515

Filed: 30 May 2007

Title: Method and Apparatus for Printing Patterns with Improved

CD Uniformity

MAIL STOP AMENDMENT Commissioner for Patents P.O. Box 1450

Alexandria, VA 22313-1450

Group Art Unit: 1756

Examiner: Unassigned

CUSTOMER NO. 22470

INFORMATION DISCLOSURE STATEMENT

Sir or Madam:

It is requested that the information identified in this statement be considered by the Examiner and made of record in the above-identified application. This statement is not intended to represent that a search has been made or that the information cited in the statement is, or is considered to be, material to patentability as defined in 37 C.F.R. 1.56.

We call to the Examiner's attention that some of the subject matter of this disclosure is related to some of the subject matter of the following applications and patents, which have been the subject of office actions:

1. U.S. Pat. No. 7,186,486, which was subject to a rejection mailed September

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12, 2005, that can be viewed in the IFW for that patent.

- U.S. Pat. No. 7,150,949, which was subject to a rejection mailed January 26, 2006, that can be viewed in the IFW for that patent.
 - 3. U.S. Pat. Nos. 6,813,062, which continues 6,618,185.
- 4. U.S. Pat. No. 6,605,816, which was subject to a rejection mailed November 3, 2002 that can be viewed in the IFW for that patent.
- U.S. Pat. No. 6,504,644 which was subject to a rejection mailed January 25, 2002, that can be viewed in the IFW for that patent.
 - 6. U.S. Pat. No. 6,285,488.

In some circumstances, the rejection of claims pending in applications such as these may be considered material by an examiner. Similarly, allowance of claims may be considered material, if they give rise to grounds for a double patenting rejection. Applicants believe that all of the relevant material is readily available online in the IFW system.

Enclosed with this statement is a Form PTO/SB/08A. The Examiner is requested to initial the form and return it to the undersigned in accordance with M.P.F.P. 609.

Also enclosed with this statement is a copy of each cited document as required by 37 C.F.R. 1.98. If, however, this application was filed after June 30, 2003, copies of U. S. Patents and U. S. Patent Application Publications are not enclosed. (See O. G. Notice of August 5, 2003.)

For foreign language documents cited in a search report by a foreign patent office, the requirement for a concise explanation of relevance is satisfied by the submission herewith of an English language version of the search report. MPEP 609A(3).

If a written English-language translation of a non-English language document, or portion thereof, is within the possession, custody or control of, or is readily available to any individual designated in 1.56(c), a copy of the translation accompanies this statement, 37 C.F.R. 1.98(a)(3)(ii), and satisfies the requirement for a concise

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explanation of relevance, MPEP 609A(3). Since any translations submitted herewith were not performed by Applicant(s), Applicant(s) do not make any representations to their accuracy.

This statement should be considered under 37 C.F.R. 1.97(b) because it is being filed before the mailing date of the first Office Action on the merits.

Fee Authorization. The Commissioner is hereby authorized to charge underpayment of any additional fees or credit any overpayment associated with this communication to Deposit Account No. 50-0869 (MLSE 1060-1).

Respectfully submitted,

Dated: July 9, 2007 /Ernest J. Beffel, Jr./

By: Ernest J. Beffel, Jr. Reg. No. 43,489

HAYNES BEFFEL & WOLFELD LLP P.O. Box 366 751 Kelly Street Half Moon Bay, CA 94019 Telephone: (650) 712-0340 Facsimile: (650) 712-0263 U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE
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Substitute for form 1449/PTO

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use as many sheets as necessary)
Sheet 1 of 2

Complete ii Known				
Application Number	10/579,511			
Filing Date	30 May 2007			
First Named Inventor	Torbojrn Sandstrom			
Art Unit	1756			
Examiner Name	Unassigned			
Attorney Docket Number	MLSE 1060-1			

				T DOCUMENTS	
Examiner initials*	Cite No.1	Document Number Number-Kind Code ^{2 (# Anount)}	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
	A1	US- 4,822,975	04-18-1989	Torigoe	
	A2	^{US-} 4,970,546	11-13-1990	Suzuki et al.	
	A3	^{US-} 4,879,605	11-07-1989	Warkentin et al.	
	A4	^{US-} 5,103,101	04-07-1992	Berglund et al.	
	A5	^{US-} 6,717,650	04-06-2004	Jain	
	A6	^{US-} 5,340,700	08-23-1994	Chen et al.	
	A7	^{US-} 4,989,255	01-29-1991	Manns et al.	
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FOREIGN PATENT DOCUMENTS							
Examiner Initials*	Cite No.1	Foreign Patent Document	Publication Date	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages		
		Country Code ³ "Number ⁴ " Kind Code ⁵ (# known)	MM-DD-YYYY		Or Relevant Figures Appear	To	
	B1	JP 02135723 A2	05-24-1990	Nikon Corp.	Abstract only		
	B2	JP 03179357 A2	08-05-1991	Nikon Corp.	Abstract only		
	B3	WO 0193303 A2	12-06-2001	Chabala et al.			
	B4	WO 03079111 A1	09-25-2003	Tyrell et al.			
	B5	EP 1324137 A2	07-02-2003	ASML Netherlands B.V.			

Examiner	Date	
Signature	Considered	

This collection of information is required by 37 CFR 147 and 1.88. The information is required to obtain or relate a benefit by the public which is to file (and by the USFFO to proceed) an application. Confidentially its operanded by 38 U.S. C. 22 and 37 CFR 1.41. This collection is estimated to take 2 hours to complete, including authering, preparing, and submitting the completed application form to the USFFO. Time will vary depending upon the individual case. Any comments on the amount of the you require to complete the form andor suggestations for reducing this button, should be sent to the Chief Information and Trademark Office, P.O. Dox 1450, Alexandris, VA 22314-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patients, P.O. Dox 1450, Alexandris, VA 22314-1450.

If you need assistance in completing the form, call 1-800-PTO-9199 (1-800-786-9199) and select option 2.

PTO/SB/08B (07-06)

Approved for use through 09/30/2006, 0MB 0651-093 U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE

	e for form 1449/PTO			Complete if Known		
				Application Number	10/579,511	
			CLOSURE	Filing Date	30 March 2007	
STATEMENT BY APPLICANT			PPLICANT	First Named Inventor	Torbjorn Sandstrom	
	(Use as many she	ets as n	acassary)	Art Unit	1756	
	,,			Examiner Name	Unassigned	
Sheet	2	of	2	Attorney Docket Number	MLSE 1060-1	

		NON PATENT LITERATURE DOCUMENTS	
Examiner Initials*	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
	C1	PCT International Search Report and Written Opinion of the International Searching Authority for International Application No. PCT/SE2004/001701 (filed 19 November 2004), mailed 11 March 2005.	
	C2	PCT International Search Report for International Application No. PCT/SE2004/001700 (filed 19 November 2004), mailed 02 May 2005.	
	СЗ	MCCARTHY, A. M. et al. "A Novel Technique for Detecting Lithographic Defects," IEEE Transactions on Semiconductor Manufacturing, Vol.1, No. 1 p.10-15 (Feb. 1998).	
	C4	NEWMAN, T. et al. "Evaluation of OPC Mask Printing with a Raster Scan Pattern Generator," Proceedings of SPIE, Vol. 4691, Optical Microllthography XV, p.1320-1330 (July 2002).	
	C5	Rieger, M. L. et al. "Lithographic Alternatives to PSM Repair," Proceedings of SPIE, Vol. 1674, Optical/Laser Microlithography V, p.609-617 (1992).	
	C6	Rieger, M. L. et al. "Image Quality Enhancements for Raster Scan Lithography," Proceedings of SPIE, Vol. 922, Optical/Laser Microlithography, p. 55-64 (March 1988).	
	C 7	Stephanakis, A. C. et al. "Advances in 1 : 1 Optical Lithography," Proceedings of SPIE, Optical Microlithography VI, Vol. 772, p.74-85 (1987).	
	C8	WOLF, S. "Advanced Lithography," p.493-513 in Silicon Processing for the VLSI Era, Vol.1 - Process Technology, Lattice Press, Inc. (1986).	

Examiner	Date	
Signature	Considered	

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

considered, include copy or the form with next communication to applicant.

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